L Number	Hits	Search Text	DB	Time stamp
1	0	6602620.pn. and block with mask	USPAT; US-PGPUB;	2003/11/06 12:35
	1205		EPO; JPO; DERWENT; IBM_TDB	2002/11/05
-	1396	mask with pattern with magnetic	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2003/11/05
_	325	(mask with pattern with magnetic same layer record\$3 and pholithography and plasma and etch\$3 and lithography) and @ad<20000419	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2003/11/06 10:00
_	102	((mask with pattern with magnetic same layer record\$3 and pholithography and plasma and etch\$3 and lithography) and @ad<20000419) and (disc disk)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2003/11/05 14:42
-	107	((mask with pattern with magnetic same layer record\$3 and pholithography and plasma and etch\$3 and lithography) and @ad<20000419) and (disc disk)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/05 14:43
-	0	mask with pattern with magnetic same layer with record\$3 and pholithography and plasma and etch\$3 and lithography	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2003/11/05 14:45
-	0	mask with pattern with magnetic same layer and pholithography and plasma and etch\$3 and lithography	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2003/11/05 14:44
-	0	mask with pattern with magnetic same layer and pholithography	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2003/11/05 14:44
-	0	mask with pattern with magnetic and pholithography and plasma and etch\$3 and lithography	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/05 14:45
-	0	mask with pattern with magnetic and pholithography and plasma and etch\$3 and lithography	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2003/11/05 14:46
-	1117	mask with pattern with magnetic and (pholithography and plasma etch\$3 lithography)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2003/11/05 14:47
_	62	mask with pattern with magnetic and (pholithography same plasma pholithography same etch\$3 lithography same plasma)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2003/11/05 14:49
_	18	(mask with pattern with magnetic and (pholithography same plasma pholithography same etch\$3 lithography same plasma)) and @ad<20000419	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2003/11/05 14:50

[-	10	((mask with pattern with magnetic and	USPAT;	2003/11/05
		(pholithography same plasma	US-PGPUB;	14:55
		pholithography same etch\$3 lithography	EPO; JPO;	
		same plasma)) and @ad<20000419) and (disc	DERWENT;	
		disk)	IBM_TDB	
-	10	((mask with pattern with magnetic and	USPAT;	2003/11/05
		(pholithography same plasma	US-PGPUB;	14:56
		pholithography same etch\$3 lithography	EPO; JPO;	
		same plasma)) and @ad<20000419) and (disc	DERWENT;	
		disk)	IBM_TDB	
-	9	(mask with pattern with magnetic same	USPAT;	2003/11/06
		layer and (pholithography same plasma	US-PGPUB;	10:01
		plasma same etch\$3 and lithography same	EPO; JPO;	
		etch\$3)) and @ad<20000419	DERWENT;	
			IBM_TDB	
-	75	,	USPAT;	2003/11/06
		layer and (pholithography same plasma	US-PGPUB;	12:34
		plasma same etch\$3 lithography same	EPO; JPO;	
		etch\$3)) and @ad<20000419	DERWENT;	
	l		IBM_TDB	